

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Kwang Su Choe, et al.

Examiner: Marianne L. Padgett

Serial No.: 10/674,647

Art Unit: 1792

Filed: September 30, 2003

Docket: YOR920030293US1 (16818)

For: THIN BURIED OXIDES BY LOW-DOSE
OXYGEN IMPLANTATION INTO MODIFIED
SILICON

Dated: December 15, 2009

Confirmation No: 4796

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

RESPONSE UNDER 37 C.F.R. § 1.114

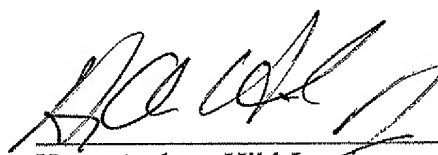
Sir:

In connection with the filing of a request for continued consideration (RCE), and in response to the Advisory Action dated November 20, 2009 and the Final Office Action dated September 15, 2009, Applicants submit the following amendments and remarks for entry as a matter of record in the above referenced application. Applicants respectfully request entry of the amendment submitted in the § 1.116 Response dated November 16, 2009. The status indicators of the present amendments indicate the status of the claim as if the amendments in the § 1.116 Response have been entered.

CERTIFICATE OF ELECTRONIC FILING

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on December 15, 2009.

Dated: December 15, 2009


Harry Andrew Hild Jr.